



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

SATO, KENICHIRO, et al.

Appln. No.: 09/541,597

Attorney Docket No.: Q58614

Confirmation No.: Not assigned

Group Art Unit: 1752

Filed: April 3, 2000

Examiner: R. ASHTON

For: POSITIVE PHOTORESIST COMPOSITION FOR FAR ULTRAVIOLET EXPOSURE

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
Washington, D.C. 20231

Sir:

This Amendment is submitted in response to the Office Action dated January 9, 2001. A Petition for a one-month extension of time is being concurrently filed, making a response due on or before May 9, 2001. Please amend the above-identified application as follows:

IN THE CLAIMS:

Please enter the following amended claims:

1 (amended). A positive photoresist composition for far ultraviolet exposure, comprising:

(A) a compound capable of generating an acid by the irradiation of an actinic ray or radiation,

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